STN Search

```
Uploading C:\Program Files\Stnexp\Queries\10080319-1.str

L2      STRUCTURE UPLOADED

=> que L2 AND L1

L3   QUE L2 AND L1

=> d
L3 HAS NO ANSWERS
L1              SCR 2067
L2              STR
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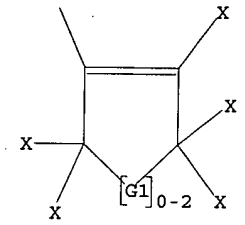


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G1 CF2,CBr2,CI2


Structure attributes must be viewed using STN Express query preparation.
L3              QUE  ABB=ON  PLU=ON  L2 AND L1


=> s l3 sss sam
SAMPLE SEARCH INITIATED 11:27:34 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED -     91 TO ITERATE

100.0% PROCESSED      91 ITERATIONS                              7 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS:  ONLINE  **COMPLETE**
                        BATCH   **COMPLETE**
PROJECTED ITERATIONS:         1248 TO     2392
PROJECTED ANSWERS:               7 TO      298

L4            7 SEA SSS SAM L2 AND L1

=> d

L4   ANSWER 1 OF 7  REGISTRY  COPYRIGHT 2003 ACS on STN
RN   430427-86-4  REGISTRY
CN   Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester,
     polymer with 2,5-furandione and octafluorocyclopentene (9CI)  (CA INDEX
     NAME)
MF   (C12 H18 O2 . C5 F8 . C4 H2 O3)x
CI   PMS
PCT  Polyother, Polyvinyl
SR   CA
LC   STN Files:   CA, CAPLUS

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     CRN  154970-45-3
     CMF  C12 H18 O2
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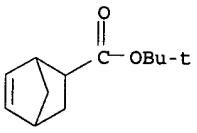


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     CRN  559-40-0
     CMF  C5 F8
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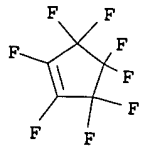
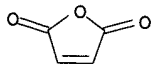


CM 3

CRN 108-31-6
CMF C4 H2 O3



1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> FIL CAPLUS HCAPLUS USPATFUL

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	2.08	2.50

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CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l4
L5 19 L4

=> s l5 and (photoresist or resist)
L6 4 L5 AND (PHOTORESIST OR RESIST)

=> d l6 1-4 ibib hitstr abs

L6 ANSWER 1 OF 4 CAPLUS COPYRIGHT 2003 ACS on STN
ACCESSION NUMBER: 2002:397839 CAPLUS
DOCUMENT NUMBER: 136:409059
TITLE: Fluorine-containing cycloolefin polymer, **photoresist** material containing the polymer, and formation of pattern
INVENTOR(S): Hatakeyama, Jun; Watanabe, Atsushi; Harada, Yuji; Kawai, Yoshio; Sasako, Masaru; Endo, Masataka; Kishimura, Shinji; Otani, Michitaka; Miyazawa, Satoru; Tsutsumi, Kentaro; Maeda, Kazuhiko
PATENT ASSIGNEE(S): Shin-Etsu Chemical Industry Co., Ltd., Japan; Matsushita Electric Industrial Co., Ltd.; Central Glass Co., Ltd.
SOURCE: Jpn. Kokai Tokkyo Koho, 25 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

5/28/02

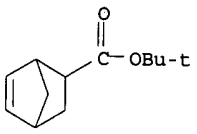
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002155120	A2	20020528	JP 2001-266772	20010904

PRIORITY APPLN. INFO.: JP 2000-271209 A 20000907
IT **430427-86-4P**
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(fluorine-contg. cycloolefin polymer for (chem.-amplified) pos.-working **photoresist**)

RN 430427-86-4 CAPLUS
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with 2,5-furandione and octafluorocyclopentene (9CI) (CA INDEX NAME)

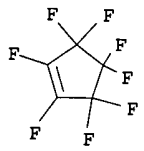
CM 1

CRN 154970-45-3
CMF C12 H18 O2



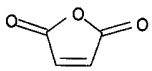
CM 2

CRN 559-40-0
CMF C5 F8

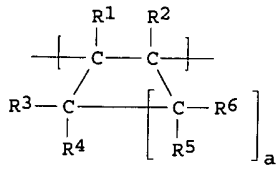


CM 3

CRN 108-31-6
CMF C4 H2 O3



GI



I

AB The polymer has a cycloolefin-derived repeating unit I (R1-R6 = H, F, Cl, C1-20 linear, branched, or cyclic alkyl, fluorinated alkyl; .gtoreq.1 of R1-R6 contain F; 0.ltoreq. a .ltoreq.10) and another repeating unit having an acid-unstable group. The **photoresist** contains the polymer and an org. solvent and an acid-generating agent may be further added to the compn. to give a chem.-amplified pos.-working **photoresist**. The compn. is applied on a substrate, heated, exposed to high energy beam at 110-190 nm or 1-15 nm wavelength through a photomask, and developed optionally after heating to give a pattern. The **photoresist** shows enhanced transparency to vacuum UV rays and dry etching resistance.

L6 ANSWER 2 OF 4 CAPLUS COPYRIGHT 2003 ACS on STN
ACCESSION NUMBER: 2001:864931 CAPLUS
DOCUMENT NUMBER: 136:12834
TITLE: Positive-working **photoresist** compositions for use under vacuum UV lasers and method for pattern formation
INVENTOR(S): Otani, Michitaka; Tsutsumi, Kentaro; Maeda, Kazuhiko

PATENT ASSIGNEE(S): Central Glass Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

11/30/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001330955	A2	20011130	JP 2000-149968	20000522

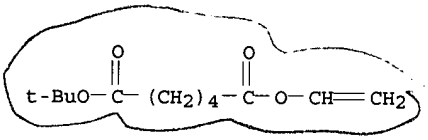
PRIORITY APPLN. INFO.: JP 2000-149968 20000522

IT **374923-68-9P**, tert-Butyl vinyl adipate-octafluorocyclopentene copolymer
RL: IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PREP (Preparation); PROC (Process); USES (Uses)
(pos.-working perfluorocyclopentene-vinyl copolymer compns. for lithog. imaging by irradn. of vacuum UV)

RN 374923-68-9 CAPLUS
CN Hexanedioic acid, 1,1-dimethylethyl ethenyl ester, polymer with octafluorocyclopentene (9CI) (CA INDEX NAME)

CM 1

CRN 374923-67-8
CMF C12 H20 O4



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CRN 559-40-0
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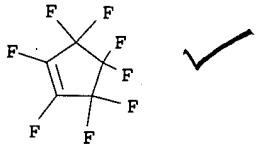

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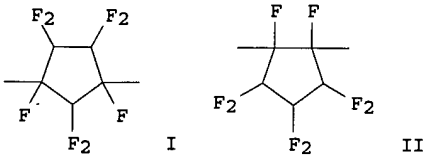

AB The compns. comprise fluoropolymers which change soly against aq. alk. soln. by reaction with acids and acid generators. The polymers consist of .gtoreq.1 mol% of structural repeating units I or II and .ltoreq.99 mol% monomers derived from vinyl compds. Preferable comonomers are also given in Markush structures. Formation of pattern is carried out by application of the compn. on a substrate, patterned exposure of the **resist** layer with light having wavelength 1-190 nm, and development of the irradiated layer. The compns. have high transparency against vacuum UV (VUV), esp. against F2 excimer lasers, and have high sensitivity.

L6 ANSWER 3 OF 4 HCAPLUS COPYRIGHT 2003 ACS on STN
ACCESSION NUMBER: 2002:397839 HCAPLUS
DOCUMENT NUMBER: 136:409059
TITLE: Fluorine-containing cycloolefin polymer, **photoresist** material containing the polymer, and formation of pattern
INVENTOR(S): Hatakeyama, Jun; Watanabe, Atsushi; Harada, Yuji;

Kawai, Yoshio; Sasako, Masaru; Endo, Masataka; Kishimura, Shinji; Otani, Michitaka; Miyazawa, Satoru; Tsutsumi, Kentaro; Maeda, Kazuhiko

PATENT ASSIGNEE(S): Shin-Etsu Chemical Industry Co., Ltd., Japan; Matsushita Electric Industrial Co., Ltd.; Central Glass Co., Ltd.

SOURCE: Jpn. Kokai Tokkyo Koho, 25 pp.
CODEN: JKXXAF

DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

5/28/02

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002155120	A2	20020528	JP 2001-266772	20010904

PRIORITY APPLN. INFO.: JP 2000-271209 A 20000907

IT **430427-86-4P**
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(fluorine-contg. cycloolefin polymer for (chem.-amplified) pos.-working **photoresist**)

RN 430427-86-4 HCAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with 2,5-furandione and octafluorocyclopentene (9CI) (CA INDEX NAME)

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CRN 154970-45-3
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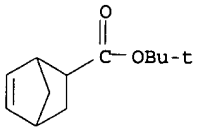

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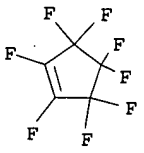
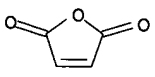
CRN 559-40-0
CMF C5 F8



CM 3

CRN 108-31-6
CMF C4 H2 O3



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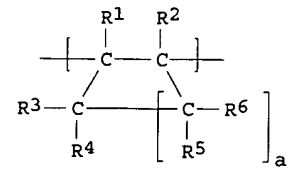


I

AB The polymer has a cycloolefin-derived repeating unit I (R1-R6 = H, F, Cl, C1-20 linear, branched, or cyclic alkyl, fluorinated alkyl; .gtoreq.1 of R1-R6 contain F; 0.ltoreq. a .ltoreq.10) and another repeating unit having an acid-unstable group. The **photoresist** contains the polymer and an org. solvent and an acid-generating agent may be further added to the compn. to give a chem.-amplified pos.-working **photoresist**. The compn. is applied on a substrate, heated, exposed to high energy beam at 110-190 nm or 1-15 nm wavelength through a photomask, and developed optionally after heating to give a pattern. The **photoresist** shows enhanced transparency to vacuum UV rays and dry etching resistance.

L6 ANSWER 4 OF 4 HCAPLUS COPYRIGHT 2003 ACS on STN
ACCESSION NUMBER: 2001:864931 HCAPLUS
DOCUMENT NUMBER: 136:12834
TITLE: Positive-working **photoresist** compositions for use under vacuum UV lasers and method for pattern formation
INVENTOR(S): Otani, Michitaka; Tsutsumi, Kentaro; Maeda, Kazuhiko
PATENT ASSIGNEE(S): Central Glass Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001330955	A2	20011130	JP 2000-149968	20000522

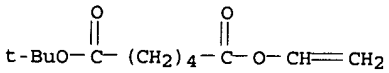
PRIORITY APPLN. INFO.: JP 2000-149968 20000522

IT **374923-68-9P**, tert-Butyl vinyl adipate-octafluorocyclopentene copolymer
RL: IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PREP (Preparation); PROC (Process); USES (Uses)
(pos.-working perfluorocyclopentene-vinyl copolymer compns. for lithog. imaging by irradn. of vacuum UV)

RN 374923-68-9 HCAPLUS
CN Hexanedioic acid, 1,1-dimethylethyl ethenyl ester, polymer with octafluorocyclopentene (9CI) (CA INDEX NAME)

CM 1

CRN 374923-67-8
CMF C12 H20 O4



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CRN 559-40-0
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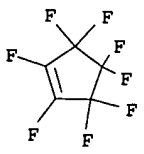
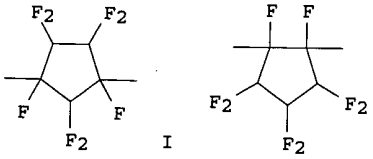


GI



I

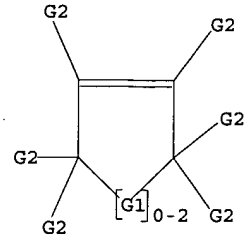
II

AB The compns. comprise fluoropolymers which change soly against aq. alk. soln. by reaction with acids and acid generators. The polymers consist of .gtoreq.1 mol% of structural repeating units I or II and .ltoreq.99 mol% monomers derived from vinyl compds. Preferable comonomers are also given in Markush structures. Formation of pattern is carried out by application of the compn. on a substrate, patterned exposure of the **resist** layer with light having wavelength 1-190 nm, and development of the irradiated layer. The compns. have high transparency against vacuum UV (VUV), esp. against F2 excimer lasers, and have high sensitivity.

PROJECTED ITERATIONS: 536511 TO 556249
PROJECTED ANSWERS: 649 TO 1535

L10 2 SEA SSS SAM L8 AND L7

=> d 19
L9 HAS NO ANSWERS
L7 SCR 2067
L8 STR



G1 CF2,CBr2,CI2

G2 CF2,CF3,CCl2,CCl3,CBr2,CBr3,CI2,CI3,Cl,Br,F,I,X

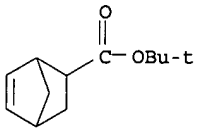
Structure attributes must be viewed using STN Express query preparation.
L9 QUE ABB=ON PLU=ON L8 AND L7

=> d l10

L10 ANSWER 1 OF 2 REGISTRY COPYRIGHT 2003 ACS on STN
RN 430427-86-4 REGISTRY
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with 2,5-furandione and octafluorocyclopentene (9CI) (CA INDEX NAME)
MF (C12 H18 O2 . C5 F8 . C4 H2 O3)x
CI PMS
PCT Polyother, Polyvinyl
SR CA
LC STN Files: CA, CAPLUS

CM 1

CRN 154970-45-3
CMF C12 H18 O2



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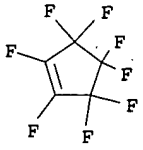

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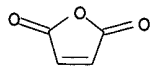
CRN 108-31-6
CMF C4 H2 O3



1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> FIL CAPLUS HCAPLUS USPATFUL
COST IN U.S. DOLLARS

	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	2.08	31.49

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)	SINCE FILE ENTRY	TOTAL SESSION
CA SUBSCRIBER PRICE	0.00	-2.60

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FILE 'HCAPLUS' ENTERED AT 11:32:38 ON 22 SEP 2003
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FILE 'USPATFULL' ENTERED AT 11:32:38 ON 22 SEP 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l10
L11 5 L10

=> d his

(FILE 'HOME' ENTERED AT 11:26:15 ON 22 SEP 2003)

FILE 'REGISTRY' ENTERED AT 11:27:08 ON 22 SEP 2003
L1 SCREEN 2067
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 7 S L3 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL' ENTERED AT 11:27:56 ON 22 SEP 2003
L5 19 S L4
L6 4 S L5 AND (PHOTORESIST OR RESIST)

FILE 'HOME' ENTERED AT 11:29:06 ON 22 SEP 2003

FILE 'REGISTRY' ENTERED AT 11:31:41 ON 22 SEP 2003
L7 SCREEN 2067
L8 STRUCTURE UPLOADED
L9 QUE L8 AND L7

FILE 'REGISTRY' ENTERED AT 11:32:10 ON 22 SEP 2003
L10 2 S L9 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL' ENTERED AT 11:32:38 ON 22 SEP 2003
L11 5 S L10

=> s l11 not l6
L12 3 L11 NOT L6

=> d l12 1-3 ibib hitstr abs

L12 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2003 ACS on STN
ACCESSION NUMBER: 2001:326291 CAPLUS
DOCUMENT NUMBER: 134:341129
TITLE: Fluoropolymers having saturated perfluoro rings with good solubility in organic solvents and their manufacture
INVENTOR(S): Akama, Hidehiro; Sugimoto, Hiromi; Tsutsumi, Kentaro
PATENT ASSIGNEE(S): Central Glass Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 2
PATENT INFORMATION:

5/8/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001122928	A2	20010508	JP 2000-232570	20000801

PRIORITY APPLN. INFO.: JP 1999-231687 A 19990818

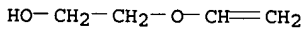
IT **337488-50-3P**, Hydroxyethyl vinyl ether-isobutyl vinyl ether-octafluorocyclopentene copolymer
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(manuf. of fluoropolymers having satd. perfluoro rings with good soly. in org. solvents for transparent films)

RN 337488-50-3 CAPLUS

CN Ethanol, 2-(ethenyloxy)-, polymer with 1-(ethenyloxy)-2-methylpropane and octafluorocyclopentene (9CI) (CA INDEX NAME)

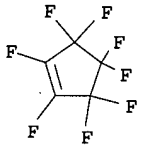
CM 1

CRN 764-48-7
CMF C4 H8 O2



CM 2

CRN 559-40-0
CMF C5 F8



CM 3

CRN 109-53-5
CMF C6 H12 O

AB The fluoropolymers (av. mol. wt. 1000-1,000,000; measured by gel permeation chromatog.), useful for transparent films, coatings, etc., contain repeating units of (A) 1-99 mol% 1,3- or 1,2-perfluorocyclopentylene and (B) 1-99 mol% divalent org. groups. Thus, an acetone soln. of vinyl acetate-octafluorocyclopentene copolymer was applied on a glass plate and dried to give a transparent film.

L12 ANSWER 2 OF 3 HCAPLUS COPYRIGHT 2003 ACS on STN
ACCESSION NUMBER: 2001:326291 HCAPLUS
DOCUMENT NUMBER: 134:341129
TITLE: Fluoropolymers having saturated perfluoro rings with good solubility in organic solvents and their manufacture
INVENTOR(S): Akama, Hidehiro; Sugimoto, Hiromi; Tsutsumi, Kentaro
PATENT ASSIGNEE(S): Central Glass Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 2
PATENT INFORMATION:

5/8/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001122928	A2	20010508	JP 2000-232570	20000801

PRIORITY APPLN. INFO.: JP 1999-231687 A 19990818

IT **337488-50-3P**, Hydroxyethyl vinyl ether-isobutyl vinyl ether-octafluorocyclopentene copolymer
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

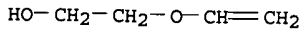
(manuf. of fluoropolymers having satd. perfluoro rings with good soly. in org. solvents for transparent films)

RN 337488-50-3 HCAPLUS

CN Ethanol, 2-(ethenyloxy)-, polymer with 1-(ethenyloxy)-2-methylpropane and octafluorocyclopentene (9CI) (CA INDEX NAME)

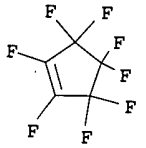
CM 1

CRN 764-48-7
CMF C4 H8 O2



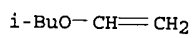
CM 2

CRN 559-40-0
CMF C5 F8



CM 3

CRN 109-53-5
CMF C6 H12 O



AB The fluoropolymers (av. mol. wt. 1000-1,000,000; measured by gel permeation chromatog.), useful for transparent films, coatings, etc., contain repeating units of (A) 1-99 mol% 1,3- or 1,2-perfluorocyclopentylene and (B) 1-99 mol% divalent org. groups. Thus, an acetone soln. of vinyl acetate-octafluorocyclopentene copolymer was applied on a glass plate and dried to give a transparent film.

L12 ANSWER 3 OF 3 USPATFULL on STN

ACCESSION NUMBER:	2002:137125 USPATFULL
TITLE:	Fluorine-containing copolymer and composition for preparing low reflectance film
INVENTOR(S):	Akama, Shuyo, Saitama, JAPAN Sugimoto, Hiromi, Saitama, JAPAN Tsutsumi, Kentaro, Saitama, JAPAN
PATENT ASSIGNEE(S):	Central Glass Company, Limited, Ube, JAPAN (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6403744	B1	20020611
APPLICATION INFO.:	US 2000-640536		20000817 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-231687	19990818
	JP 2000-84628	20000324

DOCUMENT TYPE:	Utility
FILE SEGMENT:	GRANTED
PRIMARY EXAMINER:	Zitomer, Fred
LEGAL REPRESENTATIVE:	Crowell & Moring LLP
NUMBER OF CLAIMS:	19
EXEMPLARY CLAIM:	1
NUMBER OF DRAWINGS:	6 Drawing Figure(s); 6 Drawing Page(s)
LINE COUNT:	954

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT **337488-50-3P**, Hydroxyethyl vinyl ether-isobutyl vinyl ether-octafluorocyclopentene copolymer
(manuf. of fluoropolymers having satd. perfluoro rings with good soly. in org. solvents for transparent films)

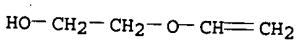
6/11/02

8/17/00 ~ 102(e)

RN 337488-50-3 USPATFULL
CN Ethanol, 2-(ethenyloxy)-, polymer with 1-(ethenyloxy)-2-methylpropane and octafluorocyclopentene (9CI) (CA INDEX NAME)

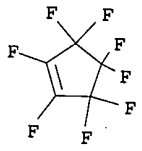
CM 1

CRN 764-48-7
CMF C4 H8 O2



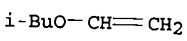
CM 2

CRN 559-40-0
CMF C5 F8



CM 3

CRN 109-53-5
CMF C6 H12 O



AB The invention relates to a fluorine-containing copolymer. This copolymer contains 1-99 mol % of a special first repeating unit of a cyclic perfluoro group; and 99-1 mol % of a second repeating unit of a bivalent organic group. The copolymer has a number average molecular weight of from 1,000 to 1,000,000 determined in a gel permeation chromatography using polystyrene as a standard material thereof. The invention further relates to a composition for forming a low reflectance film. This composition contains as a film-forming component a fluorine-containing polymer containing the first repeating unit. This polymer can be the above copolymer. A film formed by applying the composition to a substrate provides low reflectance and is improved in hardness.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

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=> file reg
COST IN U.S. DOLLARS                                    SINCE FILE      TOTAL
                                                          ENTRY    SESSION
FULL ESTIMATED COST                                        0.21       0.21

FILE 'REGISTRY' ENTERED AT 11:34:17 ON 22 SEP 2003
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STRUCTURE FILE UPDATES:   21 SEP 2003  HIGHEST RN 590345-44-1
DICTIONARY FILE UPDATES:  21 SEP 2003  HIGHEST RN 590345-44-1

TSCA INFORMATION NOW CURRENT THROUGH JULY 14, 2003

  Please note that search-term pricing does apply when
  conducting SmartSELECT searches.

Crossover limits have been increased.  See HELP CROSSOVER for details.

Experimental and calculated property data are now available.  See HELP
PROPERTIES for more information.  See STNote 27, Searching Properties
in the CAS Registry File, for complete details:
http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf

=> s octafluorocylcopentene
             0 OCTAFLUOROCYLCOPENTENE
L1           0 OCTAFLUOROCYLCOPENTENE

=> s octafluoropentane
L2          41 OCTAFLUOROPENTANE

=> s hexafluorocyclopentene
L3          20 HEXAFLUOROCYCLOPENTENE

=> s hexafluorocyclobutene
L4          15 HEXAFLUOROCYCLOBUTENE

=> s octafluorocyclopentene
L5          37 OCTAFLUOROCYCLOPENTENE

=> s l2 or l4 or l5
L6          90 L2 OR L4 OR L5

=> d

L6   ANSWER 1 OF 90  REGISTRY  COPYRIGHT 2003 ACS on STN
RN   568587-28-0  REGISTRY
CN   2-Propenoic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester,
     polymer with (ethenyloxy)cyclohexane, octafluorocyclopentene and
     2,2,2-trifluoro-1-(trifluoromethyl)ethyl 2-(trifluoromethyl)-2-propenoate
     (9CI)  (CA INDEX NAME)
MF   (C8 H14 O . C8 H11 F3 O2 . C7 H3 F9 O2 . C5 F8)x
CI   PMS
PCT  Polyacrylic, Polyother, Polyvinyl
SR   CA
LC   STN Files:   CA, CAPLUS

     CM   1

     CRN  105935-24-8
     CMF  C8 H11 F3 O2
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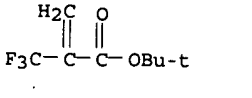

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     CMF  C7 H3 F9 O2
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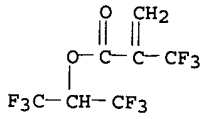
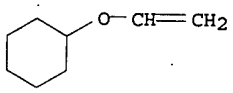


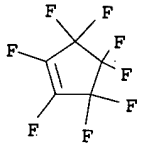
CM 3

CRN 2182-55-0
CMF C8 H14 O



CM 4

CRN 559-40-0
CMF C5 F8



1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

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=> FIL CAPLUS HCAPLUS USPATFUL
COST IN U.S. DOLLARS                                SINCE FILE      TOTAL
                                                       ENTRY    SESSION
FULL ESTIMATED COST                                    23.98      24.19

FILE 'CAPLUS' ENTERED AT 11:35:57 ON 22 SEP 2003
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FILE 'HCAPLUS' ENTERED AT 11:35:57 ON 22 SEP 2003
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FILE 'USPATFULL' ENTERED AT 11:35:57 ON 22 SEP 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l6
L7         1620 L6

=> s l7 and (photoresist or resist)
L8          143 L7 AND (PHOTORESIST OR RESIST)

=> s l8 and (?acid (w) generator)
L9           15 L8 AND (?ACID (W) GENERATOR)

=> s l9 and solvent
L10           7 L9 AND SOLVENT

=> duplicates remove l10
DUPLICATE PREFERENCE IS 'CAPLUS, HCAPLUS, USPATFULL'
KEEP DUPLICATES FROM MORE THAN ONE FILE?  Y/(N):n
PROCESSING COMPLETED FOR L10
L11            3 DUPLICATE REMOVE L10 (4 DUPLICATES REMOVED)

=> d l11 1-3 ibib hitstr

L11  ANSWER 1 OF 3  CAPLUS  COPYRIGHT 2003 ACS on STN  DUPLICATE 1
ACCESSION NUMBER:         2003:77400  CAPLUS
```

DOCUMENT NUMBER: 138:145061
TITLE: **Photoresist** monomers, polymers thereof and **photoresist** compositions containing the same
INVENTOR(S): Lee, Geun Su; Jung, Jae Chang; Shin, Ki Soo
PATENT ASSIGNEE(S): S. Korea
SOURCE: U.S. Pat. Appl. Publ., 12 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

1/30/03

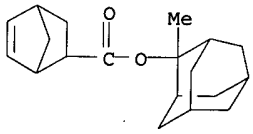
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2003022101	A1	20030130	US 2002-80319	20020221

2/21/02 present application

PRIORITY APPLN. INFO.: KR 2001-38026 A 20010629
OTHER SOURCE(S): MARPAT 138:145061
IT **492469-83-7P 492469-85-9P 492469-88-2DP**,
4-Acetoxystyrene-hexafluorocyclobutene copolymer, hydrolyzed and reaction product with ethylvinylether
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(**photoresist** monomers and polymers for **photoresist** compns.)
RN 492469-83-7 CAPLUS
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with hexafluorocyclobutene (9CI) (CA INDEX NAME)

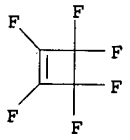
CM 1

CRN 328087-85-0
CMF C19 H26 O2



CM 2

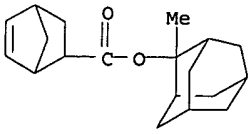
CRN 697-11-0
CMF C4 F6



RN 492469-85-9 CAPLUS
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester, polymer with 2-ethyltricyclo[3.3.1.13,7]dec-2-yl 2-propenoate and octafluorocyclopentene (9CI) (CA INDEX NAME)

CM 1

CRN 328087-85-0
CMF C19 H26 O2



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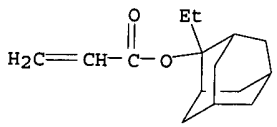
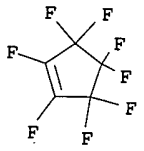
CRN 303186-14-3
CMF C15 H22 O2



CM 3

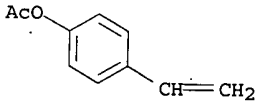
CRN 559-40-0
CMF C5 F8



RN 492469-88-2 CAPLUS
CN Phenol, 4-ethenyl-, acetate, polymer with hexafluorocyclobutene (9CI) (CA INDEX NAME)

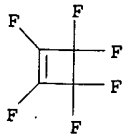
CM 1

CRN 2628-16-2
CMF C10 H10 O2



CM 2

CRN 697-11-0
CMF C4 F6



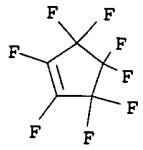
L11 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 2
ACCESSION NUMBER: 2003:5311 CAPLUS
DOCUMENT NUMBER: 138:63829
TITLE: **Photoresist** monomers, polymers thereof and **photoresist** compositions containing the same
INVENTOR(S): Lee, Geun Su; Jung, Jae Chang; Shin, Ki Soo
PATENT ASSIGNEE(S): S. Korea
SOURCE: U.S. Pat. Appl. Publ., 13 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2003003379	A1	20030102	US 2002-79348	20020220
JP 2003040931	A2	20030213	JP 2002-122435	20020424

not to another!

2/20/03

PRIORITY APPLN. INFO.: KR 2001-34603 A 20010619
IT **559-40-0**
RL: RCT (Reactant); RACT (Reactant or reagent)
(prepn. fluoropolymer for **photoresist** compns.)
RN 559-40-0 CAPLUS
CN Cyclopentene, octafluoro- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)

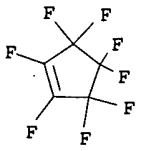


L11 ANSWER 3 OF 3 USPATFULL on STN
ACCESSION NUMBER: 2003:10537 USPATFULL
TITLE: Polymers, **resist** compositions and patterning process
INVENTOR(S): Harada, Yuji, Nakakubiki-gun, JAPAN
Watanabe, Jun, Nakakubiki-gun, JAPAN
Hatakeyama, Jun, Nakakubiki-gun, JAPAN
Kawai, Yoshio, Nakakubiki-gun, JAPAN
Sasago, Masaru, Hirakata-shi, JAPAN
Endo, Masayuki, Izumi-shi, JAPAN
Kishimura, Shinji, Itami-shi, JAPAN
Ootani, Michitaka, Kawagoe-shi, JAPAN
Miyazawa, Satoru, Kawagoe-shi, JAPAN
Tsutsumi, Kentaro, Kawagoe-shi, JAPAN
Maeda, Kazuhiko, Chiyoda-ku, JAPAN
PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Tokyo, JAPAN (non-U.S. corporation)

	NUMBER	KIND	DATE	
PATENT INFORMATION:	US 2003008231	A1	20030109	
APPLICATION INFO.:	US 2002-84828	A1	20020228	(10)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2001-53664	20010228
	JP 2001-53669	20010228

DOCUMENT TYPE: Utility
FILE SEGMENT: APPLICATION
LEGAL REPRESENTATIVE: MILLEN, WHITE, ZELANO & BRANIGAN, P.C., 2200 CLARENDON BLVD., SUITE 1400, ARLINGTON, VA, 22201
NUMBER OF CLAIMS: 9
EXEMPLARY CLAIM: 1
LINE COUNT: 1461
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT **559-40-0**, Octafluorocyclopentene
(F-contg. group-contg. polymers for chem. amplified pos.-working resists and their use in pattern formation)
RN 559-40-0 USPATFULL
CN Cyclopentene, octafluoro- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)



2/28/02

not prior art

=> d l20 1-3 ibib hitstr

L20 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 1
ACCESSION NUMBER: 2003:626408 CAPLUS
DOCUMENT NUMBER: 139:157393
TITLE: Fluorine-containing **photoresist** with reaction anchor for chemical amplification and improved copolymerization characteristics
INVENTOR(S): Rottstegge, Joerg
PATENT ASSIGNEE(S): Infineon Technologies A.-G., Germany
SOURCE: Ger. Offen., 14 pp.
CODEN: GWXXBX
DOCUMENT TYPE: Patent
LANGUAGE: German
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
DE 10203838	A1	20030814	DE 2002-10203838	20020131
US 2003157432	A1	20030821	US 2003-356791	20030131

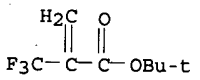
PRIORITY APPLN. INFO.: DE 2002-10203838 A 20020131

1/31/03

IT **572922-00-0P**
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(fluorine-contg. **photoresist** with reaction anchor for chem. amplification and improved copolymn. characteristics)
RN 572922-00-0 CAPLUS
CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer with decafluorocyclohexene and 3a,4,7,7a-tetrahydro-1,3-isobenzofurandione (9CI) (CA INDEX NAME)

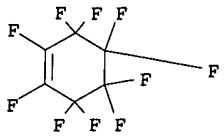
CM 1

CRN 105935-24-8
CMF C8 H11 F3 O2



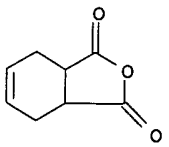
CM 2

CRN 355-75-9
CMF C6 F10



CM 3

CRN 85-43-8
CMF C8 H8 O3



L20 ANSWER 2 OF 3 USPATFULL on STN
ACCESSION NUMBER: 2003:225620 USPATFULL
TITLE: Fluorine-containing **photoresist** having reactive anchors for chemical amplification and

improved copolymerization properties
INVENTOR(S): Rottstegge, Jorg, Lilienthal, GERMANY, FEDERAL REPUBLIC OF

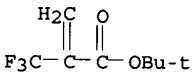
	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003157432	A1	20030821
APPLICATION INFO.:	US 2003-356791	A1	20030131 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	DE 2002-10203838	20020131

DOCUMENT TYPE: Utility
FILE SEGMENT: APPLICATION
LEGAL REPRESENTATIVE: LERNER AND GREENBERG, P.A., POST OFFICE BOX 2480, HOLLYWOOD, FL, 33022-2480
NUMBER OF CLAIMS: 14
EXEMPLARY CLAIM: 1
LINE COUNT: 871
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT **572922-00-0P**
(fluorine-contg. photoresist with reaction anchor for chem. amplification and improved copolymn. characteristics)
RN 572922-00-0 USPATFULL
CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer with decafluorocyclohexene and 3a,4,7,7a-tetrahydro-1,3-isobenzofurandione (9CI) (CA INDEX NAME)

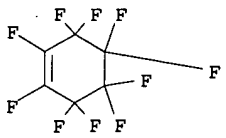
CM 1

CRN 105935-24-8
CMF C8 H11 F3 O2



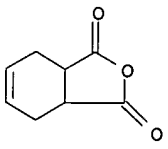
CM 2

CRN 355-75-9
CMF C6 F10



CM 3

CRN 85-43-8
CMF C8 H8 O3



L20 ANSWER 3 OF 3 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 2
ACCESSION NUMBER: 2002:868986 CAPLUS
DOCUMENT NUMBER: 137:370796
TITLE: Radiation-sensitive polysiloxane resin composition
INVENTOR(S): Iwasawa, Haruo; Hayashi, Akihiro; Shimokawa, Tsutomu; Yamamoto, Masafumi
PATENT ASSIGNEE(S): JSR Co., Ltd., Japan
SOURCE: PCT Int. Appl., 155 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent

LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2002090423	A1	20021114	WO 2002-JP4333	20020430

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM

RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

JP 2003020335	A2	20030124	JP 2002-48643	20020225

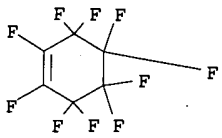
PRIORITY APPLN. INFO.: JP 2001-133795 A 20010501
JP 2002-48643 A 20020225

OTHER SOURCE(S): MARPAT 137:370796

IT **355-75-9**, Decafluorocyclohexene
RL: RCT (Reactant); RACT (Reactant or reagent)
(radiation-sensitive polysiloxane resin compn.)

RN 355-75-9 CAPLUS

CN Cyclohexene, decafluoro- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)



REFERENCE COUNT: 25 THERE ARE 25 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

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